ABSTRACT

METHOD FOR PRODUCING SILICEOUS FILM AND POLYSILAZANE COATING TREATMENT LIQUID USED THEREFOR

The present invention provides a method for forming a siliceous film. According to the method, a siliceous film having a hydrophilic surface can be formed from a polysilazane compound at a low temperature. In the method, a composition containing a polysilazane compound and a silica-conversion reaction accelerator is applied on a substrate surface to form a polysilazane film, and then a polysilazane film-treatment solution is applied thereon so that the polysilazane compound can be converted into a siliceous film at 300°C or less. The polysilazane film-treatment solution contains a solvent, hydrogen peroxide and an alcohol.

Nil